

[DOCUMENT NAME] WRITTEN ABSTRACT

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[PROBLEM TO BE SOLVED]

To reduce the bending amount caused by Coulomb force of electrodes and obtain uniformity of surface processing in a plasma processing apparatus for a workpiece having a large area.

[SOLUTION MEANS]

An electrode structure 30X of a plasma processing apparatus comprises a pair of electrode rows 31X, 32X extending leftward and rightward and opposite to each other in back and forth directions. Each electrode row includes a plurality of electrode members 31A through 32C bilaterally arranged in a side-by-side relation. The electrode members of the two electrode rows, which are bilaterally arranged in substantially same positions, have opposite polarities and form row-to-row partial gaps 33p therebetween. The electrode members arranged adjacent to each other are opposite in polarity with respect to each other.